

Licht als kleinstes Reagenz und Werkzeug

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Grundlagenuntersuchungen zum Mechanismus kurzlebiger Zustände führen in der Photochemie zum Verständnis der Wirkprinzipien; von diesen Erkenntnissen profitieren die industriellen Anwendungen in Medizin, Chemikaliensynthese, Drucktechnik, chemische Trocknung sowie zur Reinigung und Entgiftung.

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